

PATENT 8074-1143

## IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Koichi NANIWAE

Conf. unknown

Application No. 10/573,492

Group unknown

Filed March 24, 2006

Examiner unknown

METHOD OF CLEANING TREATMENT AND METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

June 27, 2006

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying document, a copy of which is attached to this statement, is made of record on the enclosed sheet.

A concise explanation of the relevance of this item is that this reference is discussed on pages 3 and 4 of the present specification.

Respectfully submitted,

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				Filing Date: March 24, 2006			Group Art Unit: <b>unknown</b>			
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